

IBM endstation

Beamline: BXDS

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An endstation optimized for investigating transformations of thin films and multilayers during rapid thermal treatments in-situ.

- Samples can be rapidly heated to 1273 K (+1000 °C) under vacuum or ultra high purity gas such as He or N₂.
- X-ray diffraction measurements with a linear strip detector. 640 pixels of 125 μm x 8 mm, a maximum count rate of 10^5 Hz per pixel, and 30 ms minimum readout time.
- In-situ roughness and 4-point resistance probes.
- Robotic sample loading (up to 96 at one time), automated, remote access is default.

